

Electronic Supplementary Information

Bias Stress Stable Aqueous Solution Derived Y-Doped ZnO

Thin Film Transistors

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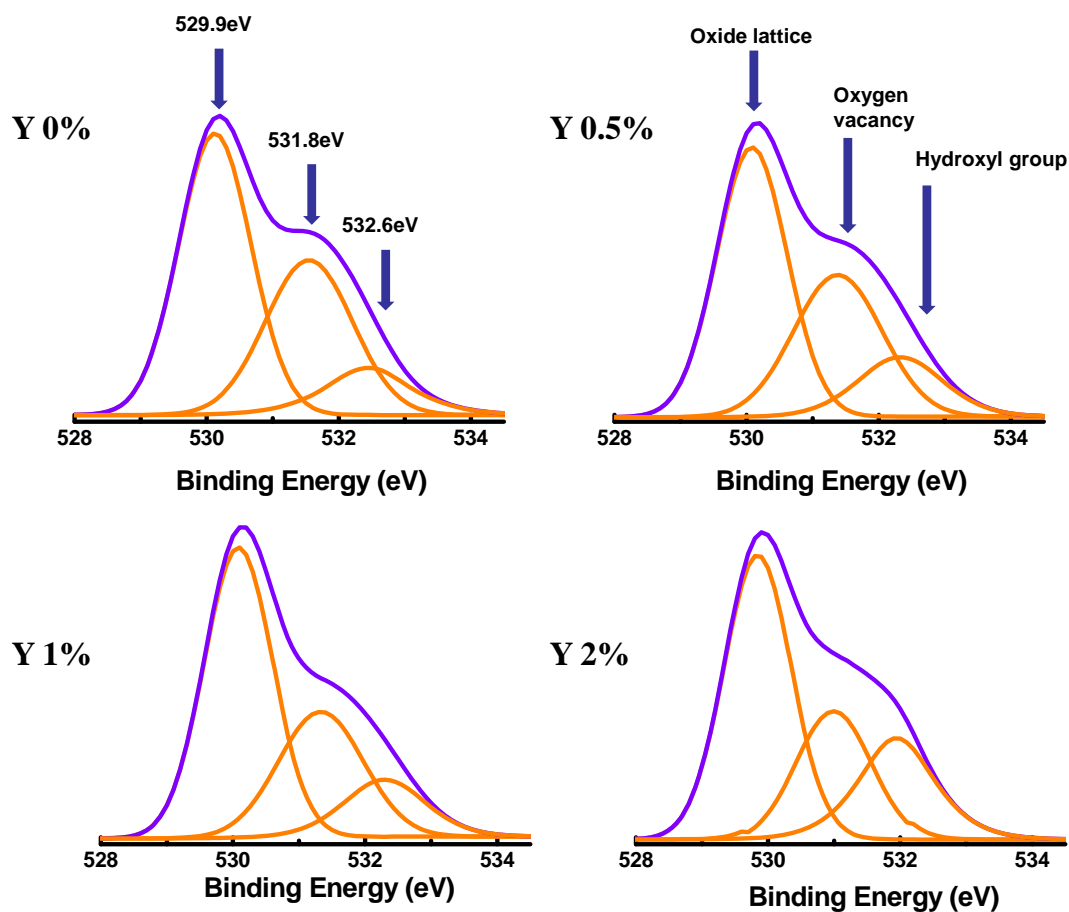


Fig. S1. XPS spectra of the O1s core level line for the solution processed YZO films as a function of Y content.

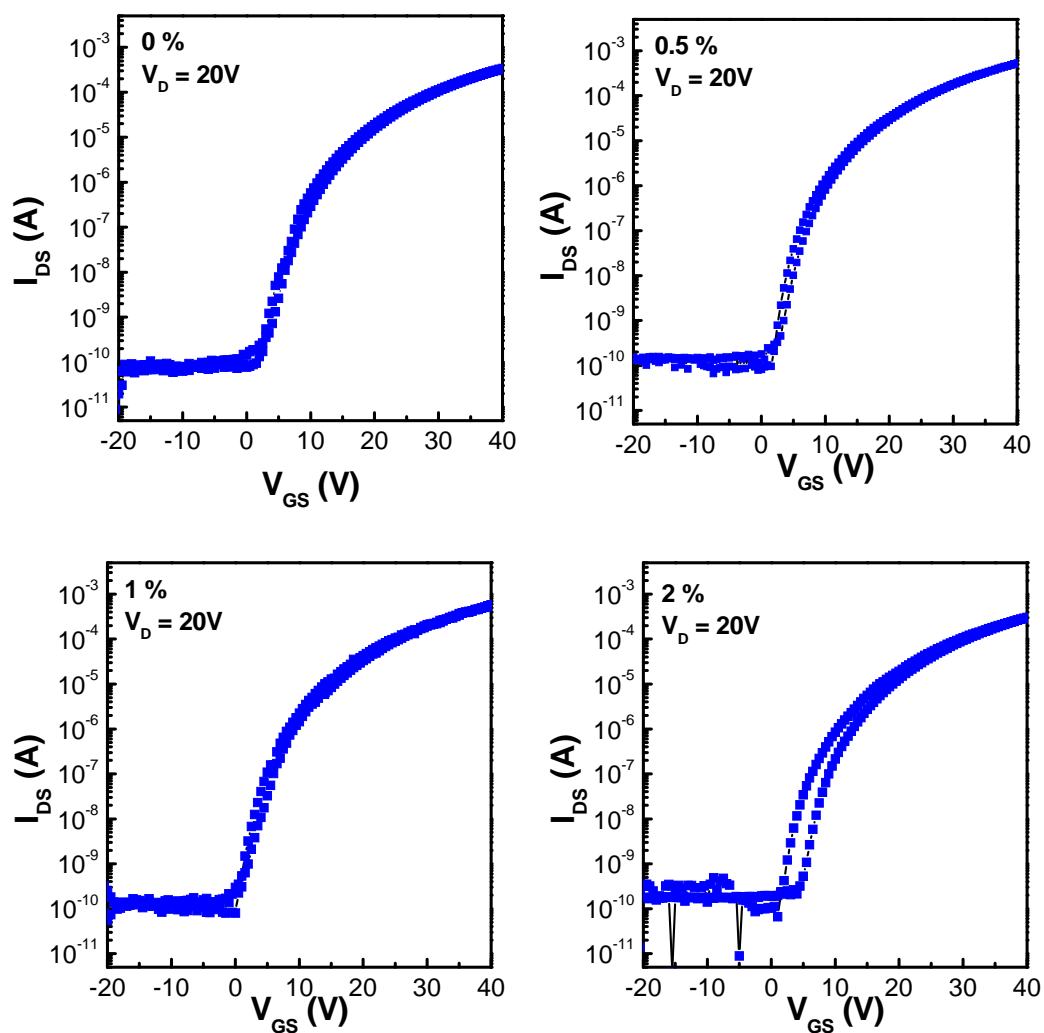


Fig. S2. Transfer characteristics of YZO TFTs as a function of Y doping concentration.

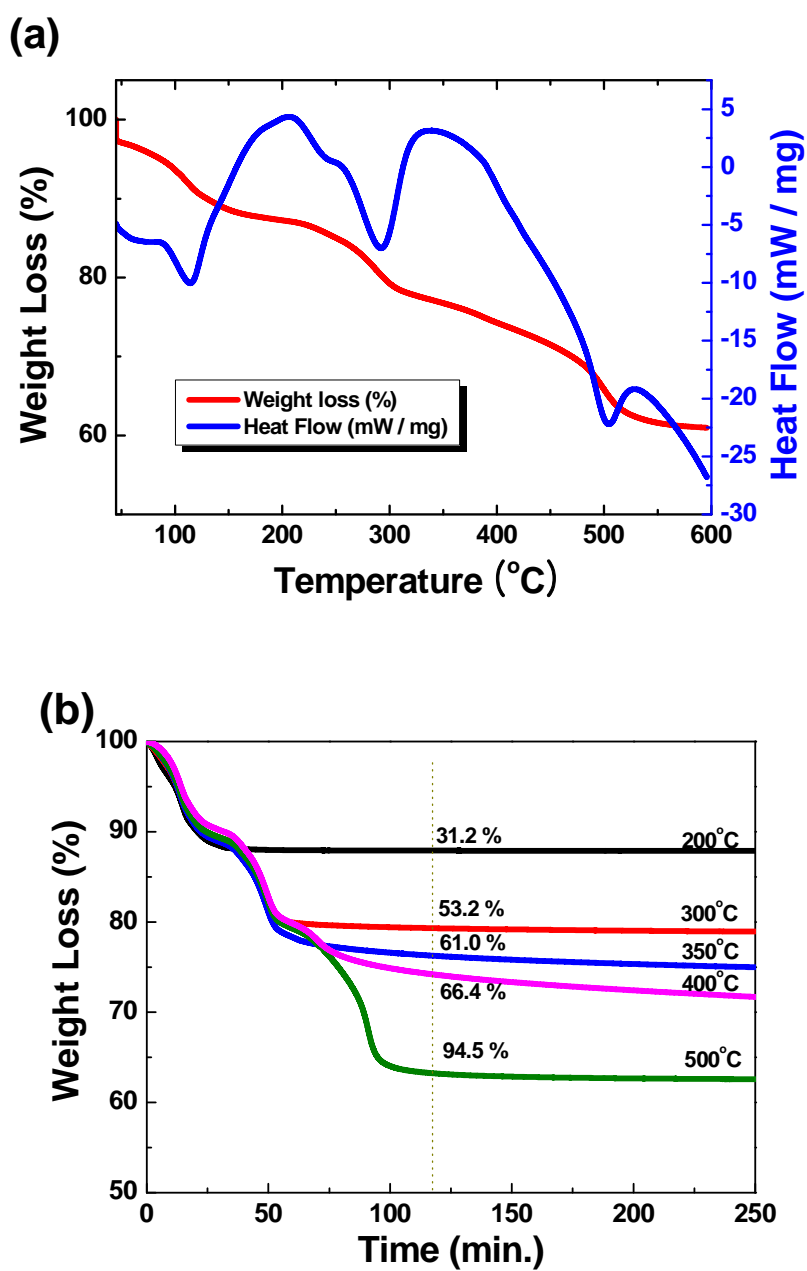


Fig. S3. (a) Thermogravimetric analysis (TGA) and differential scanning calorimetry (DSC) and (b) thermal behavior as a function of temperature ranging from 200 °C to 500 °C of the as-prepared $\text{Y}(\text{OH})_3$ powder. The numbers in (b) indicate the dehydration percentage for $\text{Y}(\text{OH})_3$. These values were calculated using the ratio of weight loss after 2 h at a specific temperature in (b) to the weight loss at 600 °C (it is considered that a complete dehydration of $\text{Y}(\text{OH})_3$ occurs at 600 °C as shown in (a)).

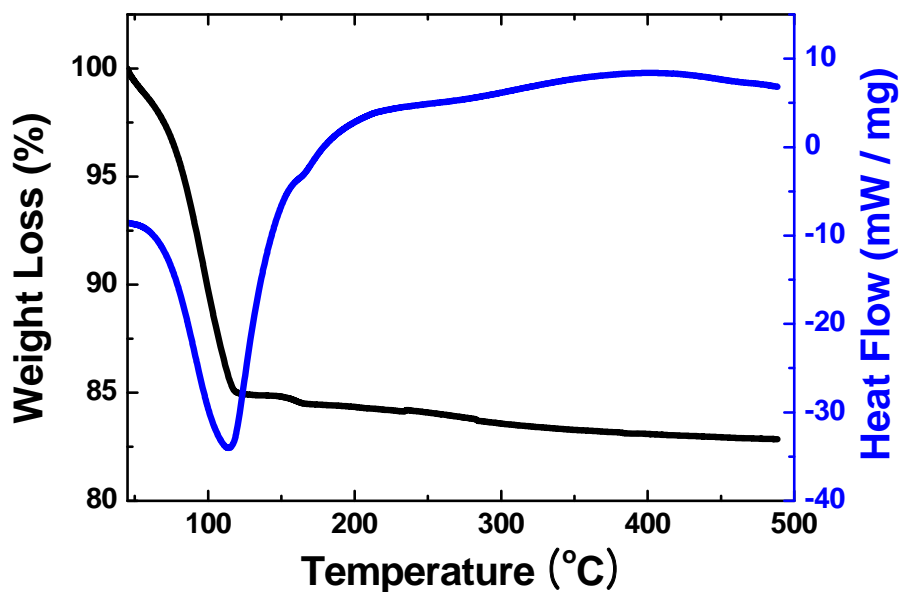


Fig. S4. Thermogravimetric analysis (TGA) and differential scanning calorimetry (DSC) of Zn(OH)_2 powder.

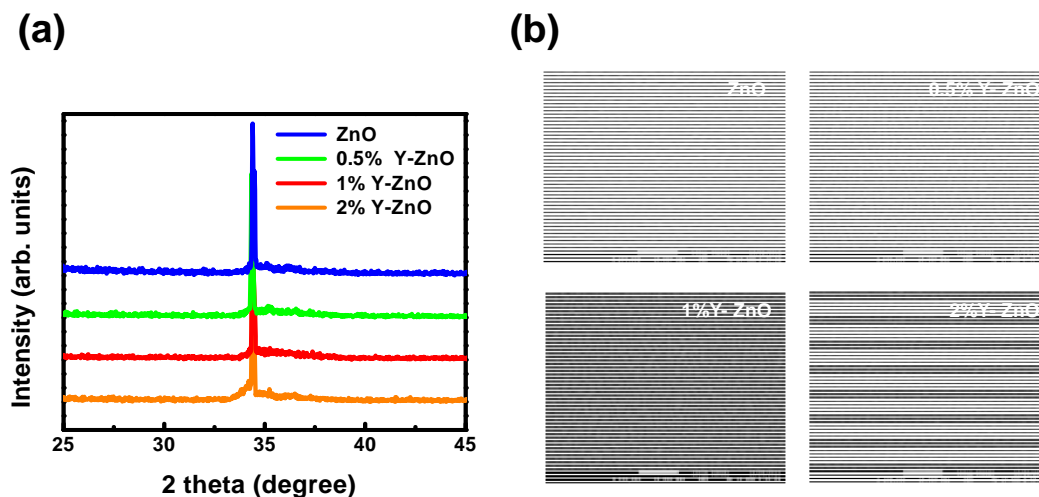


Fig. S5. (a) XRD patterns of ZnO and YZO films deposited on silicon substrate. Film thickness was ~ 150 nm. (b) Representative SEM top-view images of ZnO and YZO films as a function of Y doping concentration. Scale bar = 100 nm.

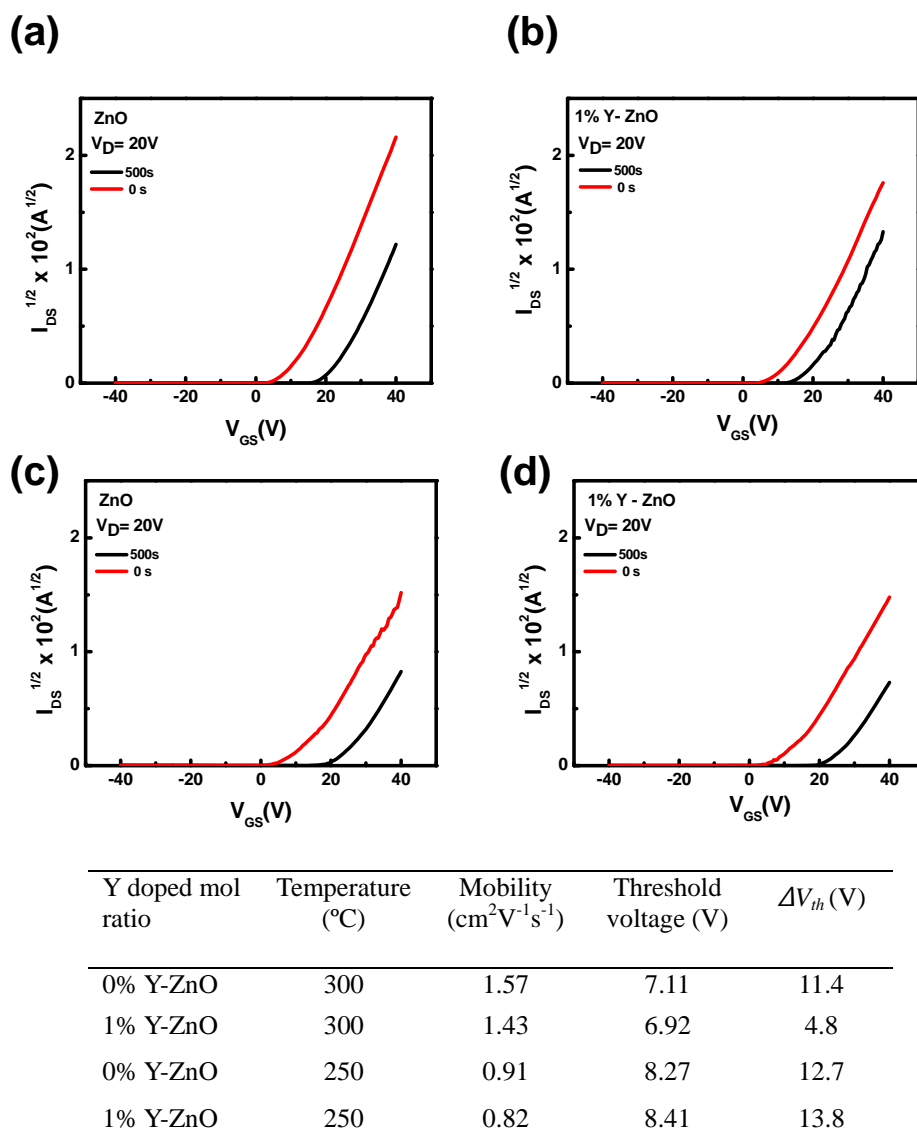


Fig. S6. The $\sqrt{I_D}$ vs V_G plot to extract the threshold voltage shift for the spin-coated YZO-TFTs fabricated on $\text{SiO}_2/\text{n}^+\text{-Si}$ substrates as a function of Y doped ratio. (a) and (b) samples were annealed at 300 °C. (c) and (d) samples were annealed at 250 °C. The bias instability was analyzed under a positive bias stress.